Form PTO-1449			Sheet 1 of 2
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hy	1~		4/98	Ghosh et al.		1.56	89		Appropriate
╟─┼─	AE	+	8/97	Ribier et al. ,		424	401	+	
	AC		8/00	Lee et al.		264	1.54	+	
	AD AE	5,597,613	1/97	Galameau et al.		427	162	+	
hy	AF	6,190,929 B1 6,225,143 B1	2/01	Wang et al.		438	20	 	
0-9	AG	0,223,143 BI	5/01	Rao et al.		438	106		
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		U.S. PATENT DOCUMENTS		

U.S. PATENT DOCUMENTS *Examiner Document Date Number Name Class Subclass Filing Date If Appropriate AA ΑB AC AD ΑE ΑF AG ΑH FOREIGN PATENT DOCUMENTS Document Number Subclass Translation No ΑJ OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) Website: http://www.dow.com/cyclotene/over.htm: Cyclotene: BCB Properties; 5/14/01 ΑK hy Website: http://www.dow.com/cyclotene/over/tg.htm: Tg vs Cure; 5/14/01 "New polymer materials for nanoimprinting"; H. Schulz et al.; J. Vac. Sci. Techol. B18(4) July/Aug 2000; pp. 1861-1865 AN **EXAMINER** DATE CONSIDERED 65/03

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